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Inventor: Gars J. Derderian et al.

Title: **Atomic Layer Deposition Methods, and Methods of Forming Materials Over Semiconductor Substrates**

Assignee: **Micron Technology, Inc.**

Serial No.: **10/671,922**

Filed: **September 24, 2003 [RCE Filed Herewith]**

INFORMATION DISCLOSURE STATEMENT

PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98

The attached Form PTO-1449 is submitted in compliance with 37 CFR §1.56. Pursuant to FEDERAL REGISTER, Vol. 69, No. 182, pg. 56542 (September 21, 2004), no copies of any cited U.S. patents or U.S. published applications are included herewith. No admission is made regarding whether the listed reference is prior art.

Citation of this patent is respectfully requested.

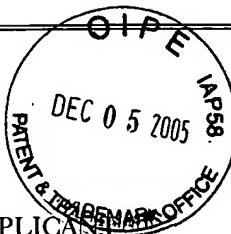
Respectfully submitted,

Dated: 12/5/03 By:



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Form PTO-1449

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MI22-2296SERIAL NO.
10/671,922APPLICANT
Garo J. Derderian et al.FILING DATE
Sept. 24, 2003 [RCE filed herewith]GROUP
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U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,812,157 B1	11/04	Gadgil			
	AB						
	AC						
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	AG						
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	AJ						

FOREIGN PATENT DOCUMENTS

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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

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